

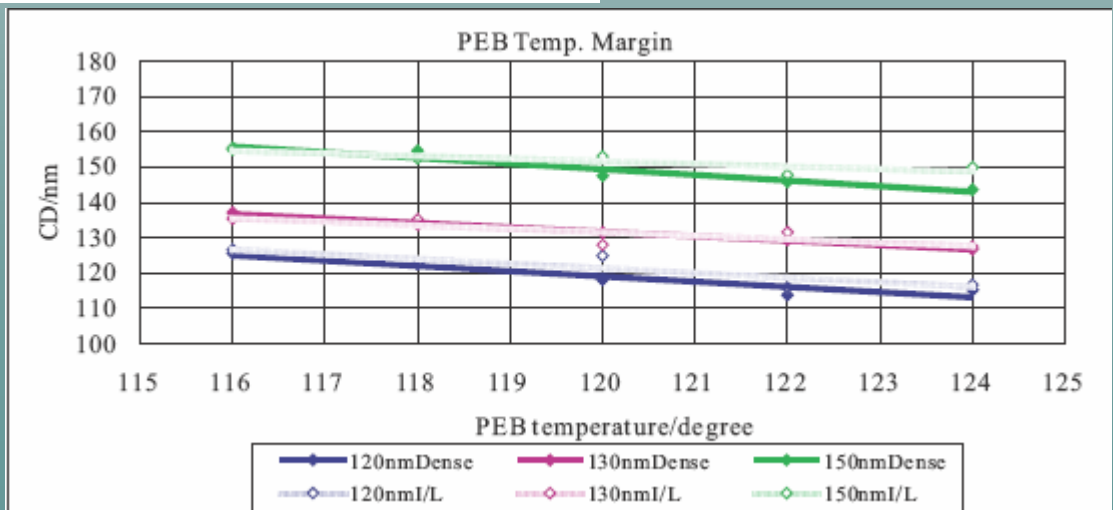
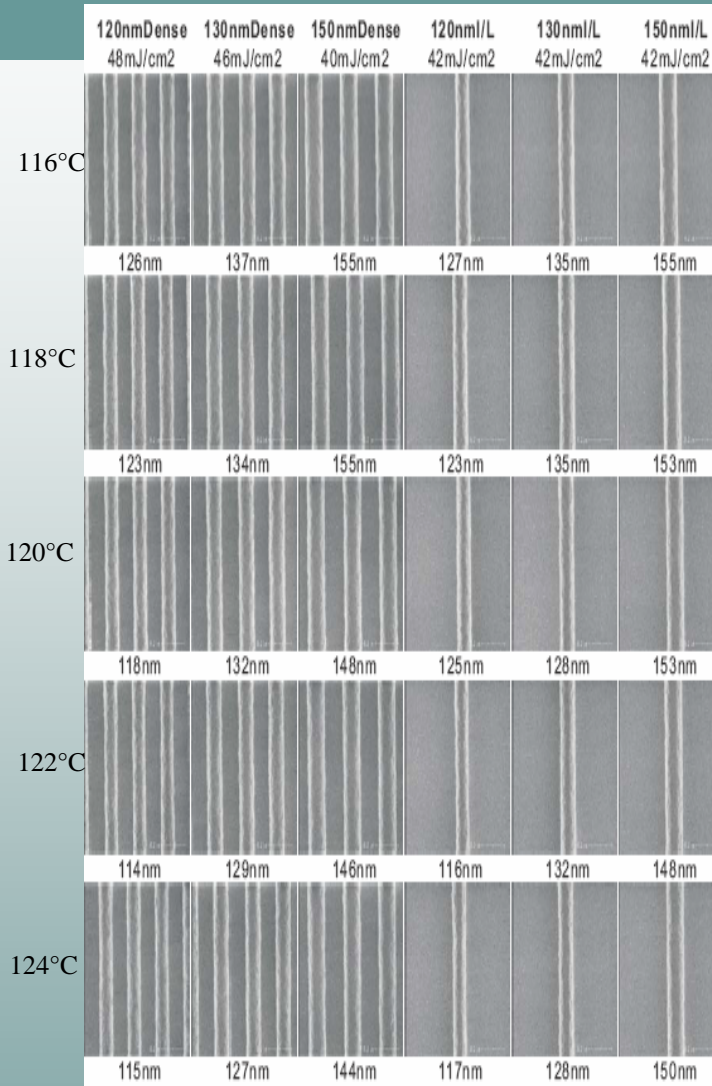


ArF Photoresist

SAIL-series

Superior PEB Temperature Margin

Substrate : ARC29A (78nm)
 Thickness : 320nm
 Soft Bake : 105°C x 60sec
 Exposure : NA=0.68, sigma=0.85,
 Mask : HT-PSM (6%)
 PEB : 120°C x 60sec
 Development : 2.38% TMAH, 30s Puddle



Substrate : ARC29A (78nm)
 Thickness : 250nm
 Soft Bake : 110°C x 60sec
 Exposure : NA=0.68, sigma=0.85,
 2/3annular
 Mask : HT-PSM (6%)
 PEB : 110°C x 60sec
 Development : 2.38% TMAH, 30s Puddle

FE-SEM : HITACHI S-9220
 Ip/HV : 8pA/300V
 Method : 32 points width measurement
 Magnification 200k

